

REPORT DOCUMENTATION PAGE			Form Approved OMB NO. 0704-0188		
<p>The public reporting burden for this collection of information is estimated to average 1 hour per response, including the time for reviewing instructions, searching existing data sources, gathering and maintaining the data needed, and completing and reviewing the collection of information. Send comments regarding this burden estimate or any other aspect of this collection of information, including suggestions for reducing this burden, to Washington Headquarters Services, Directorate for Information Operations and Reports, 1215 Jefferson Davis Highway, Suite 1204, Arlington VA, 22202-4302. Respondents should be aware that notwithstanding any other provision of law, no person shall be subject to any penalty for failing to comply with a collection of information if it does not display a currently valid OMB control number.</p> <p>PLEASE DO NOT RETURN YOUR FORM TO THE ABOVE ADDRESS.</p>					
1. REPORT DATE (DD-MM-YYYY) 25-11-2018		2. REPORT TYPE Final Report		3. DATES COVERED (From - To) 7-Apr-2016 - 6-Apr-2017	
4. TITLE AND SUBTITLE Final Report: Custom Designed Thermal Evaporator for Transformative Research and Education in Novel Thermal Management and Energy Conversion Devices Based on Nanomaterials			5a. CONTRACT NUMBER W911NF-16-1-0141		
			5b. GRANT NUMBER		
			5c. PROGRAM ELEMENT NUMBER 611103		
6. AUTHORS			5d. PROJECT NUMBER		
			5e. TASK NUMBER		
			5f. WORK UNIT NUMBER		
7. PERFORMING ORGANIZATION NAMES AND ADDRESSES Georgia Tech Research Corporation 505 Tenth Street NW Atlanta, GA 30332 -0420			8. PERFORMING ORGANIZATION REPORT NUMBER		
9. SPONSORING/MONITORING AGENCY NAME(S) AND ADDRESS (ES) U.S. Army Research Office P.O. Box 12211 Research Triangle Park, NC 27709-2211			10. SPONSOR/MONITOR'S ACRONYM(S) ARO		
			11. SPONSOR/MONITOR'S REPORT NUMBER(S) 68482-EL-RIP.1		
12. DISTRIBUTION AVAILABILITY STATEMENT Approved for public release; distribution is unlimited.					
13. SUPPLEMENTARY NOTES The views, opinions and/or findings contained in this report are those of the author(s) and should not be construed as an official Department of the Army position, policy or decision, unless so designated by other documentation.					
14. ABSTRACT					
15. SUBJECT TERMS					
16. SECURITY CLASSIFICATION OF:			17. LIMITATION OF ABSTRACT UU	15. NUMBER OF PAGES	19a. NAME OF RESPONSIBLE PERSON Baratunde Cola
a. REPORT UU	b. ABSTRACT UU	c. THIS PAGE UU			19b. TELEPHONE NUMBER 404-385-8652

RPPR Final Report

as of 26-Nov-2018

Agency Code:

Proposal Number: 68482ELRIP

Agreement Number: W911NF-16-1-0141

INVESTIGATOR(S):

Name: Baratunde A. Cola
Email: cola@gatech.edu
Phone Number: 4043858652
Principal: Y

Organization: **Georgia Tech Research Corporation**

Address: 505 Tenth Street NW, Atlanta, GA 303320420

Country: USA

DUNS Number: 097394084

EIN: 580603146

Report Date: 06-Jul-2017

Date Received: 25-Nov-2018

Final Report for Period Beginning 07-Apr-2016 and Ending 06-Apr-2017

Title: Custom Designed Thermal Evaporator for Transformative Research and Education in Novel Thermal Management and Energy Conversion Devices Based on Nanomaterials

Begin Performance Period: 07-Apr-2016

End Performance Period: 06-Apr-2017

Report Term: 0-Other

Submitted By: Baratunde Cola

Email: cola@gatech.edu

Phone: (404) 385-8652

Distribution Statement: 1-Approved for public release; distribution is unlimited.

STEM Degrees:

STEM Participants:

Major Goals: This DURIP acquisition has been placed in the Nanomaterials Floor of the Marcus Nanotechnology Building at Georgia Tech, where 3 faculty, over 30 graduate students, and more than 5 post docs, research engineers, and visiting scholars are co-located for dedicated and collaborative research spanning 4 departments: Mechanical Engineering, Materials Science and Engineering, Electrical and Computer Engineering, and Chemical and Biomolecular Engineering. The tool is available to all of these researchers, and to the more than 300 users of the facilities of the Marcus Nanotechnology Building for research and educational activities. The Marcus Nanotechnology Building is a part of the Georgia Tech Institute for Electronics and Nanotechnology (IEN). This DURIP has helped to advance carbon nanotube rectenna development, fundamental understanding of thermal and electrical transport in conjugated polymers, and launch a new area of thermoplasmonic energy conversion in nanowires.

The acquisition of our resistive thermal evaporator has been central for the research described above. A key factor in our ability to accomplish the research goals is an ability to produce reliable, controlled devices at a steady rate for the scientific studies. The acquisition of the deposition tool proposed here allows this, overcoming current rate limiting challenges at Georgia Tech. Our tool is the only at Georgia Tech that allows deposition of low work function metal for our devices without a very low yield and/or the ability to test and preserve the samples in an inert atmosphere.

Accomplishments: We purchased an Angstrom Engineering NexDep Deposition System with Integrated Glove Box that we custom designed to deliver on the goals of this DURIP. Resistive evaporation is a commonly used vacuum deposition process in which electrical energy is used to heat a filament which in turn heats a deposition material to the point of evaporation. The process can be performed at very high levels of vacuum allowing for a long mean free path and therefore fewer tendencies to introduce film impurities. High deposition rates can be achieved and lower energy particles can reduce substrate damage. Angstrom Engineering developed a thin film deposition systems based on this technique that can deposit a wide range of materials including metals, organic, and inorganic polymers. The process is controlled using quartz rate sensor, temperature, or optical monitoring systems to ensure consistent high-quality results.

We integrated a controlled atmosphere glove box to overcome our current physical vapor deposition (PVD) process challenges. This total system integration allows non-PVD and PVD processes to be connected within a controlled environment. The integrated system allows sensitive materials and substrates to be stored, then moved from process to process and tested without exposure to the open environment. This equipment is integrated with a substrate temperature controller for improved grain boundary migration, post process annealing and controlling surface reactions.

RPPR Final Report as of 26-Nov-2018

Important features of our NexDep system include:

- Support for multiple PVD processes
- Recipe based advanced multi-layer deposition control with user logon control
- Sequential or co-deposition
- Sensors are rigidly mounted to ensure calibration is maintained
- In co-deposition configurations QCM sensors are carefully isolated to ensure there is no interference from adjacent source material
- Stainless steel isolation shields help to protect sources from cross contamination
- Substrate heating and cooling
- Planetary motion
- Custom chamber height of 48 inches, which is required to minimize the interfacial degradation

After the tool was installed, several projects advanced as a result of these new capabilities and we were able to make new rectenna devices with record efficiencies of more than 10X higher than previous efforts.

Training Opportunities: Several Ph.D. students were able to use our new evaporator to advance their work. One Ph.D. student, Erik Anderson, has become an expert with the tool and gain skills in helping others with their projects.

Results Dissemination: Nothing to Report

Honors and Awards: Nothing to Report

Protocol Activity Status:

Technology Transfer: Nothing to Report

PARTICIPANTS:

Participant Type: Graduate Student (research assistant)

Participant: Erik Anderson

Person Months Worked: 3.00

Funding Support:

Project Contribution:

International Collaboration:

International Travel:

National Academy Member: N

Other Collaborators:

Nothing additional to report